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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Appl. No. : 10/624,356 : Confirmation No.: 7682
Applicant : Aaron Scott Lukas et al.
Filed : 21 July 2003
For : Non-Thermal Process for Forming Porous Low Dielectric Constant Films

Art Unit : 1771
Examiner : Victor S. Chang

Docket No. : 06336PUSA
Customer No. : 23543

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

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RESPONSE TO RESTRICTION REQUIREMENT

Sir:

The following is responsive to the Office Action dated 6/15/2005:

- ☐ Amendments to the Specification begin on page of this paper.
- ☒ Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.
- ☐ Amendments to the Drawings begin on page of this paper and include an attached replacement sheet(s).
- ☐ Amendments to the Abstract are on page of this paper. A clean version of the Abstract is on page of this paper.
- ☒ Remarks/Arguments begin on page 9 of this paper.